

EXPOSURE APPARATUS AND PRODUCTION METHOD OF DEVICE  
USING THE SAME

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ABSTRACT OF THE DISCLOSURE

10 An exposure apparatus which transfers a pattern  
image formed on a mask on to a substrate through a  
projection optical system, comprising a substrate  
table which holds said substrate, a first sensor which  
measures a gap between said substrate surface held by  
said substrate table and a control target position,  
and a second sensor which measures a distance between  
said projection optical system and said substrate  
15 table in an optical axis direction and corrects the  
control target position of said first sensor.